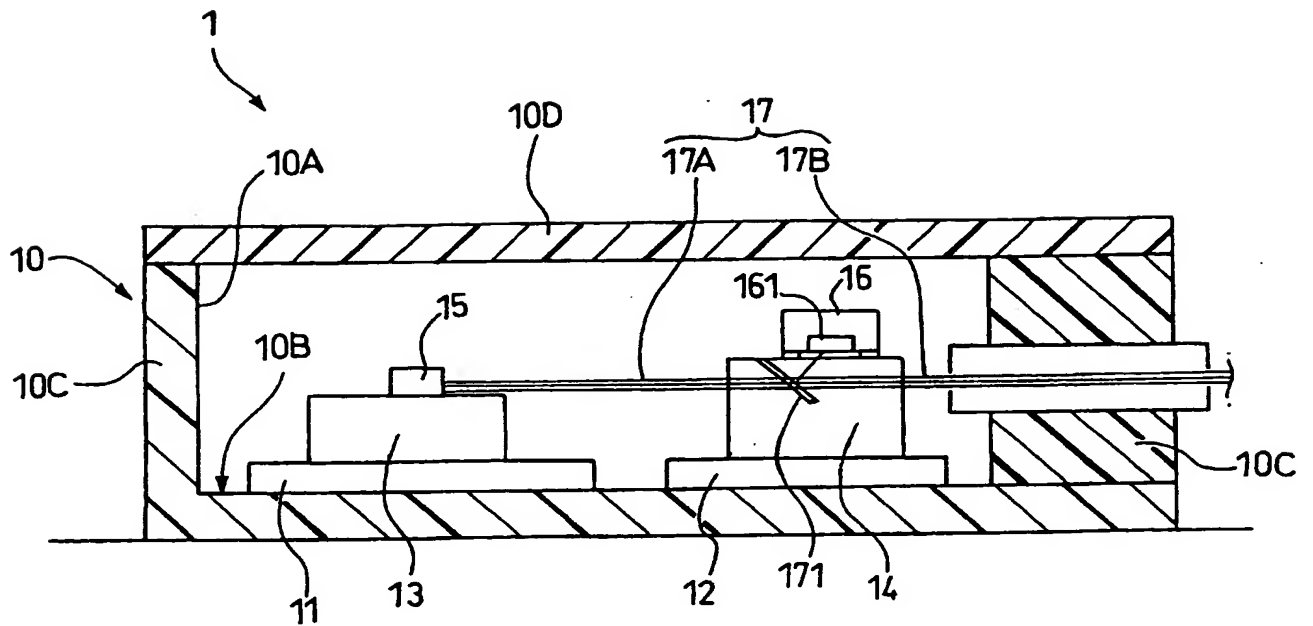


FIG. 1



[illegible]

FIG. 3 (C)

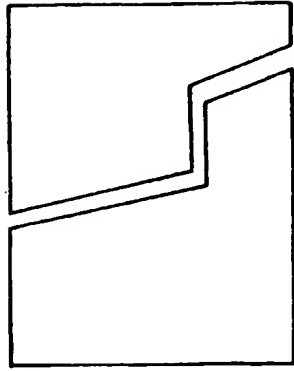


FIG. 3 (B)

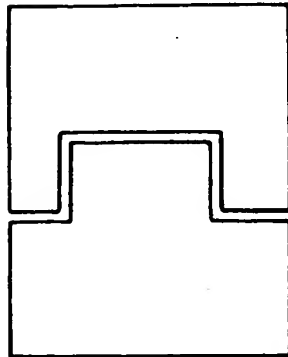


FIG. 3 (A)

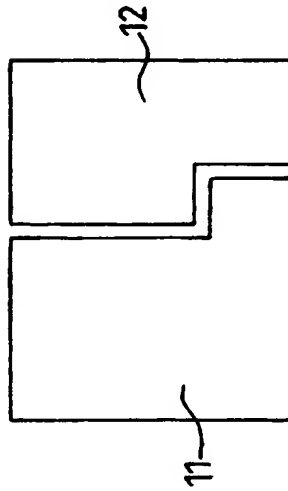


FIG. 3 (E)

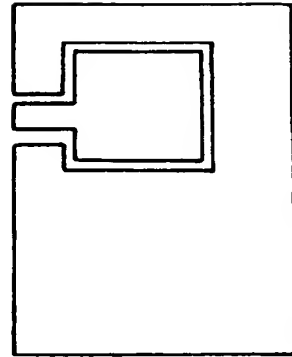
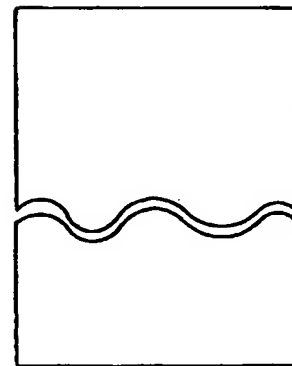
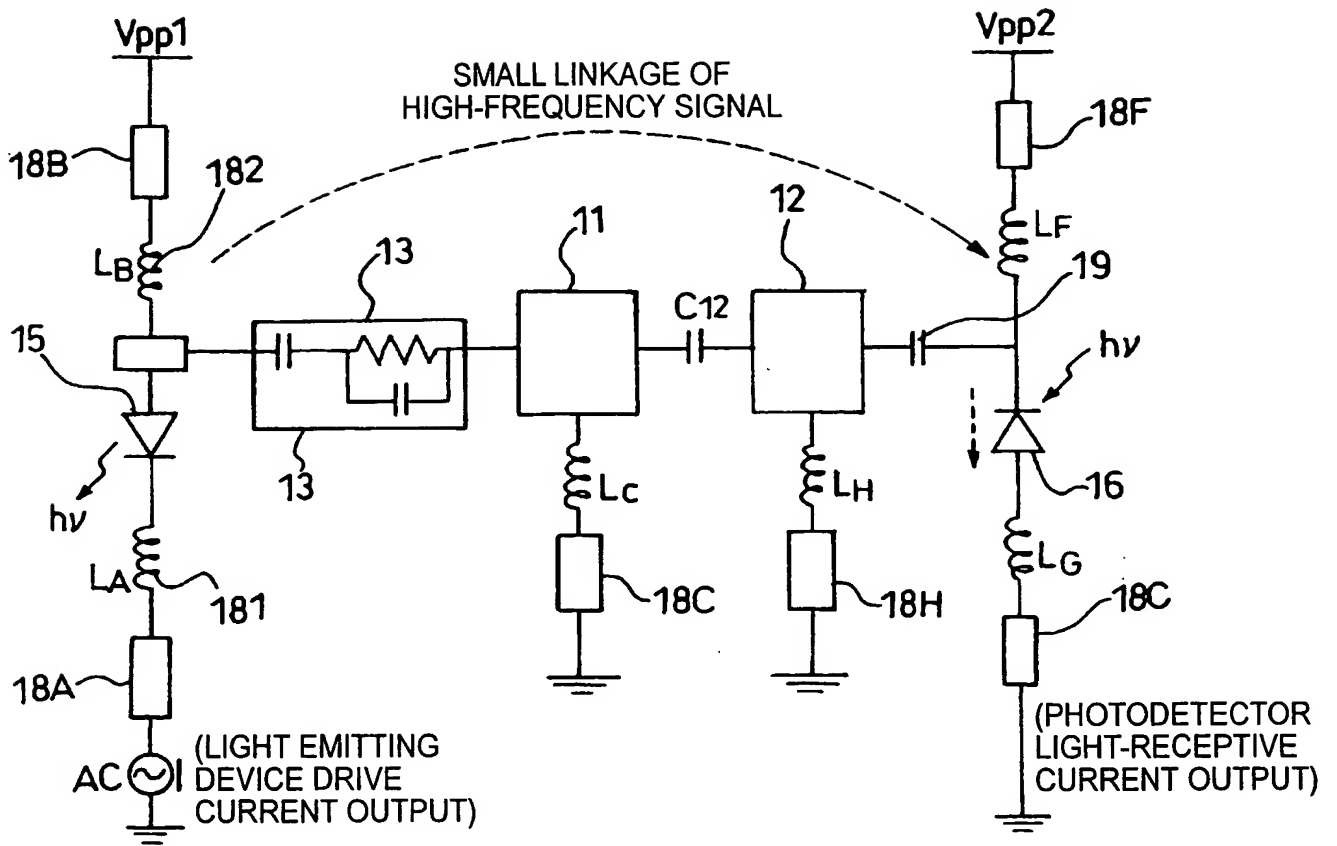


FIG. 3 (D)



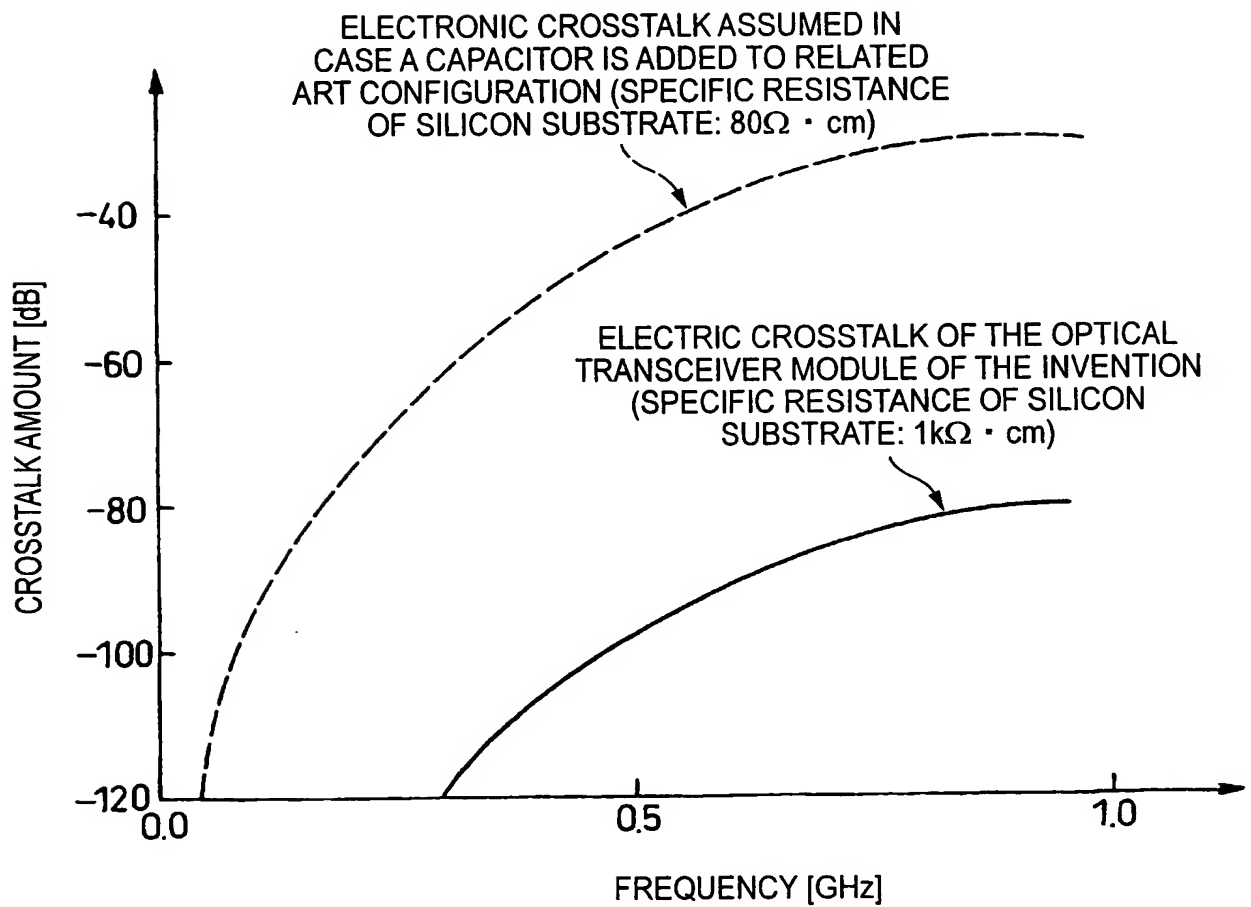
4/11

FIG. 4



5/11

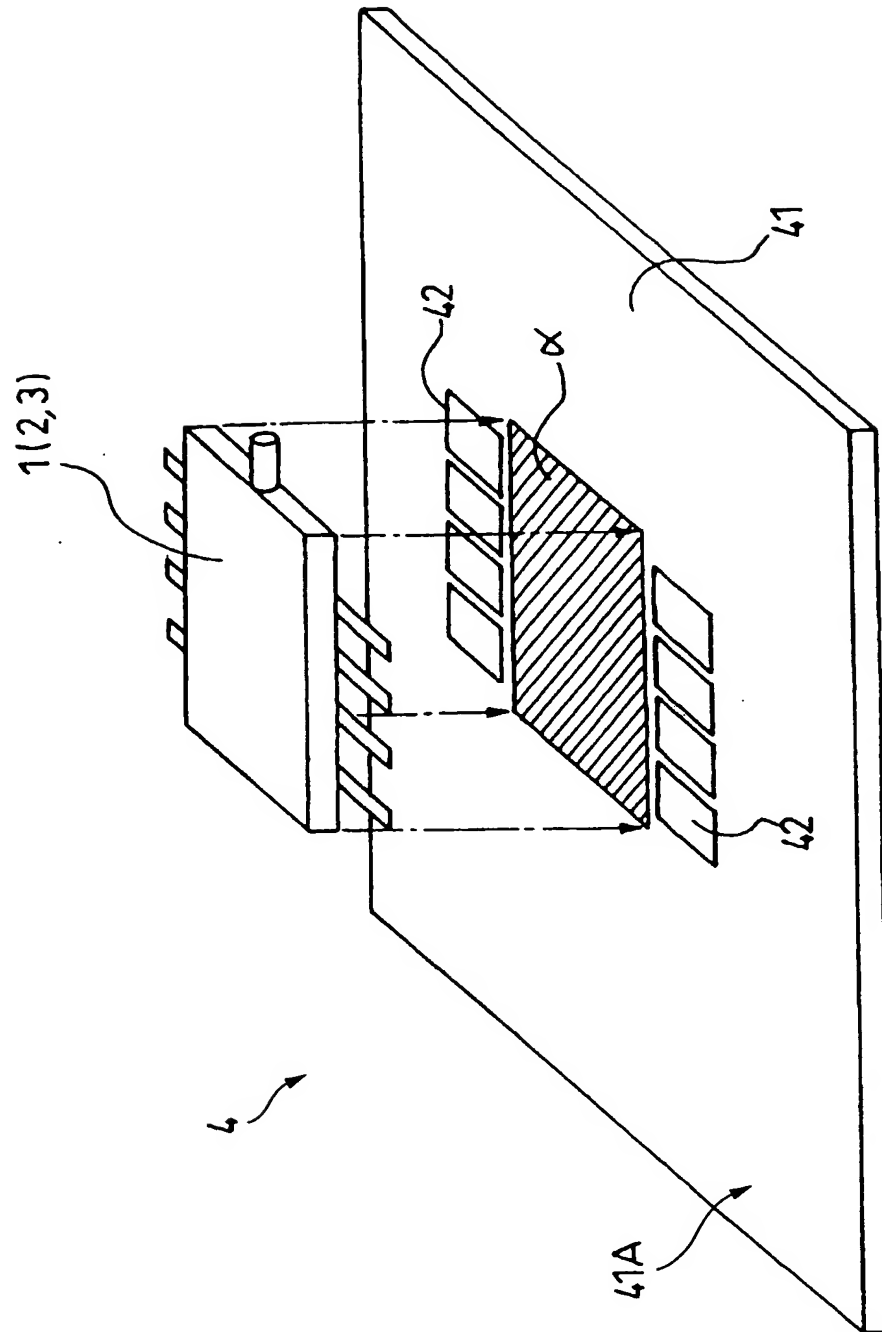
FIG. 5





A cross-sectional view of a semiconductor device 3. The device is built on a substrate 10. It features a central channel region 11 and two side regions 12. A gate stack 13 is positioned over the channel region 11, and gate stacks 14 are positioned over the side regions 12. The gate stack 13 includes a gate oxide layer 15 and a gate electrode 16. The gate stacks 14 include a gate oxide layer 17(17A) and a gate electrode 17(17B). The side regions 12 are doped with impurities, indicated by the hatching pattern. The channel region 11 is also doped with impurities, indicated by the hatching pattern. The device is surrounded by a protective layer 10C. The device is labeled 3.

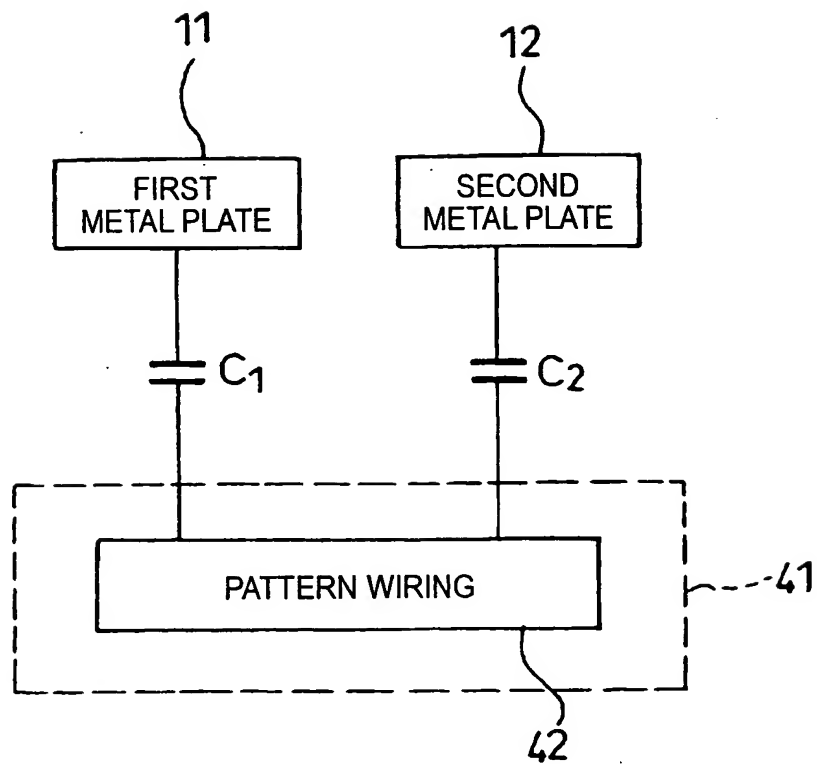
FIG. 8





9/11

FIG. 9



10/11

FIG. 10

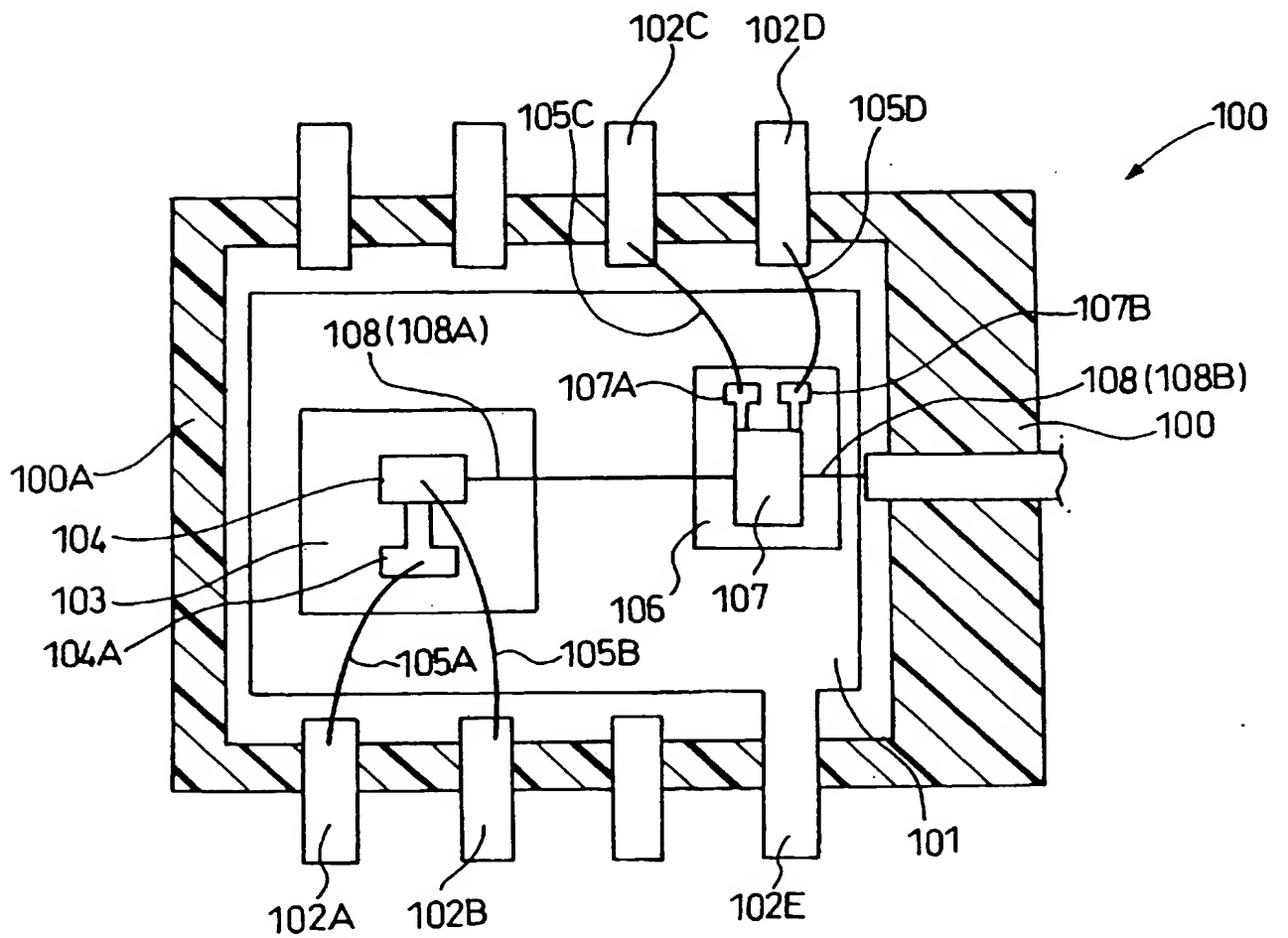


FIG. 11

